	Application No.	Applicant(s)
Notice of Allowability	10/659,889	ROBERTS ET AL.
	Examiner	Art Unit
	Anthony Ojini	3723
The MAILING DATE of this communication appears on the cover sheet with the correspondence address All claims being allowable, PROSECUTION ON THE MERITS IS (OR REMAINS) CLOSED in this application. If not included herewith (or previously mailed), a Notice of Allowance (PTOL-85) or other appropriate communication will be mailed in due course. THIS NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIGHTS. This application is subject to withdrawal from issue at the initiative of the Office or upon petition by the applicant. See 37 CFR 1.313 and MPEP 1308.		
1. This communication is responsive to <i>application filed 09/11/03</i> .		
2. The allowed claim(s) is/are <u>1-10</u> .		
3. The drawings filed on are accepted by the Examiner.		
 4.		
Attachment(s) 1. ☑ Notice of References Cited (PTO-892) 2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948) 3. ☐ Information Disclosure Statements (PTO-1449 or PTO/SB/0 Paper No./Mail Date 4. ☐ Examiner's Comment Regarding Requirement for Deposit of Biological Material	6. Interview Summar Paper No./Mail D 08), 7. Examiner's Amend	ate

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EXAMINER'S AMENDMENT

An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in a telephone interview with Attorney Konrad H. Kaeding on April 2, 2004.

The application has been amended as follows:

In claims 1,4,7, line 13, change the term "comprising" to ----consisting of: ----.

The following is an examiner's statement of reasons for allowance: the specific limitations of "a polishing pad having a hydrophilic polishing layer having a polishing surface consisting essentially of a polishing material having a density greater than 0.5 g/cm; a critical surface tension greater than or equal to 34 milliNewtons per meter; tension modulus of 0.02 to 5 GigaPascals a ratio of tensile modules at 30 C to tensile modulus at 60 C of 1.0 to 2.5; a hardness of 25 to 80 Shore D; a yield stress of 300-6000 psi; a tensile strength of 1000 to 15,000 psi; an elongation to break less than or equal to 500%, said polishing material comprising a polymer pad material selected from the group consisting of: a urethane, a carbonate, an amide, ester, acrylate, methacrylate, acrylate, methacrylate, sulfone" in the combination as claimed in claims 1,4,7, are not anticipated or made obvious by the prior art in the examiner's opinion. For example, Cook et al. (5,489,233) disclose a method of polishing a substrate, comprising: creating a plurality of micro-recesses upon a thermoplastic

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hydrophilic polishing pad having a random surface topography which is created by moving an abrasive medium against and relative to the polishing surface. However, the art of record considered alone or in combination, fails to provide or suggest "a polishing pad having a hydrophilic polishing layer having a polishing surface consisting essentially of a polishing material having a density greater than 0.5 g/cm; a critical surface tension greater than or equal to 34 milliNewtons per meter; tension modulus of 0.02 to 5

GigaPascals a ratio of tensile modules at 30 C to tensile modulus at 60 C of 1.0 to 2.5; a hardness of 25 to 80 Shore D; a yield stress of 300-6000 psi; a tensile strength of 1000 to 15,000 psi; an elongation to break less than or equal to 500%, said polishing material comprising a polymer pad material selected from the group comprising: a urethane, a carbonate, an amide, ester, acrylate, methacrylate, acrylate, methacrylate, sulfone".

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Anthony Ojini whose telephone number is 703 305 3768. The examiner can normally be reached on 7 to 4 Tuesday-Friday with every other Monday off.

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If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Joseph Hail can be reached on 703 308 2687. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Joseph J. Hail, III Supervisory Patent Examiner Technology Center 3700

AO March 24, 2004